



Contact Information

John Pong  
Nanonex Corporation  
1-732-355-1600  
jpong@nanonex.com

Release on August 10, 2006

*NANONEX DELIVERS ADVANCED NANOIMPRINT TOOL TO  
FORSCHUNGSZENTRUM JÜLICH GMBH, GERMANY*

---

**Princeton, NJ, August 10, 2006:** Nanonex Corporation, the leader in nanoimprint solution and applications with the longest history, announces today a delivery and installation of an advanced nanoimprint lithography system, the Nanonex NX-2000 to Forschungszentrum Jülich GmbH in Jülich, Germany.

Nanonex has been supplying nanoimprint solutions (tool, resists, molds, and processes) to over 70 user groups globally. Known US national labs and universities that have purchased Nanonex nanoimprint tools include Sandia National Lab, National Institute of Standard and Technology (NIST), National Nanostructure Infrastructure Network's (NNIN) node at the University of California at Santa Barbara (UCSB), the University of Michigan, the University of Maryland, and Princeton Institute for the Science and Technology of Materials (PRISM) at Princeton University.

The Nanonex NX-2000 installed at Forschungszentrum Jülich, Germany, is a versatile nanoimprint tool for both uv and thermal imprinting, with an Air Cushion Press™ (ACP) for excellent imprint uniformity and yield over large area, and with a Smart Sample Holder (SSH) for flexible imprinting of the molds and substrates having arbitrary shape and geometry (up to 4" diameter).

Dr. Andreas Rudiger of the Institute of Solid State Research at Forschungszentrum Jülich has this comment regarding their acquisition of the nanoimprinter:

“We chose the Nanonex NX2000 nanoimprint lithography tool mainly for two reasons:

Within a key technology project for nanoarchitecture design we need a versatile nanolithography tool that caters for both thermal and UV processing. The air cushion system makes a real difference as it provides maximum flexibility for the sample size and shape and to even process different samples of different dimensions simultaneously. The bottleneck of e-beam direct writing will thus be

by-passed. Within the research center we receive more and more requests for an introduction to the device.”

Larry Koecher, COO at Nanonex said that Nanonex is delighted to have placed their first advanced nanoimprint lithography system in Germany and be a nanoimprint solution provider to Forschungszentrum Jülich, and to see strong demand of Nanonex tools in Europe.

**About Nanonex Corp.**

Nanonex, a pioneer and a leader in nanoimprint, provides a complete line of nanoimprint lithography (NIL) technology solutions including tools, masks, and processes. Nanonex NIL solutions offer sub 10 nm feature resolution, 3D patterning, large area uniformity, accurate overlay alignment, high-throughput, and low cost. Nanonex NIL solutions include all forms of nanoimprinting, such as thermal plastic, uv-curable, thermal curable, and direct imprinting (embossing). Nanonex NIL solutions can meet the needs of a broad spectrum of markets, such as optical devices, displays, data storage, biotech, IC, chemical synthesis, and advanced materials. Visit [www.nanonex.com](http://www.nanonex.com) for additional information.